

# J-PARCにおける超高精度非球面 スーパーミラーの開発

原子力機構 J-PARC センター

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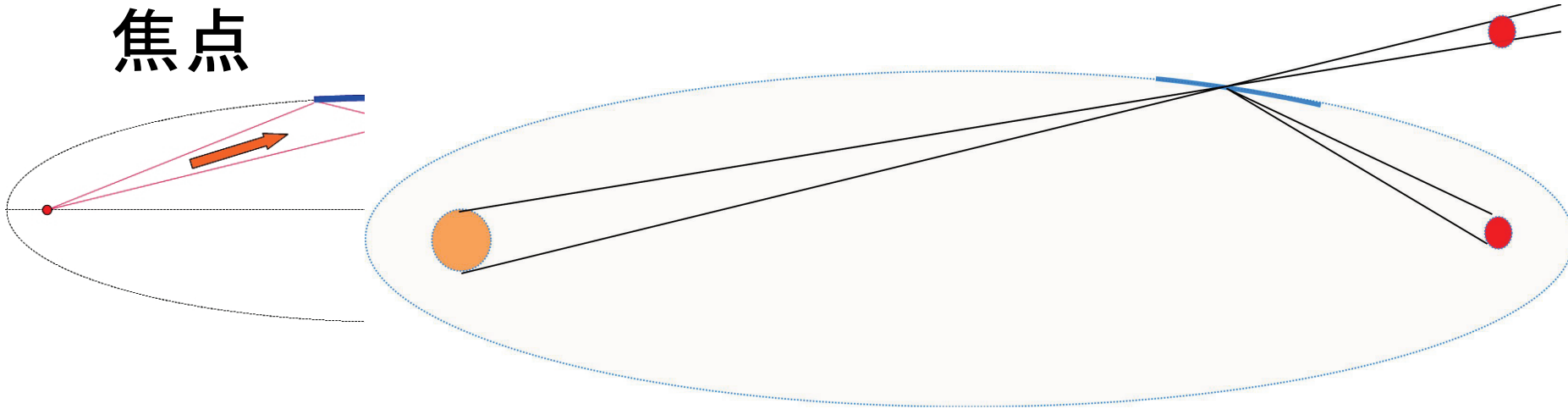
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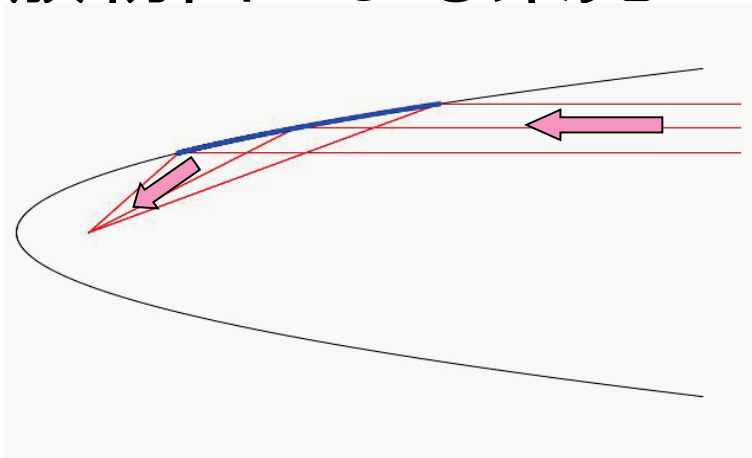
- 反射ミラー集光とその特徴
- 作成プロセス; Supermirror, NC- LWE
- 1次元集光スーパーミラーの開発
- スタック用の薄い集光スーパーミラー
- Kirkpatrick-Baez 配置での2次元集光試験n
- 適用例

# 非球面ミラーによる中性子集光

- 楕円による集光： 焦点からの発散ビーム→焦点



- 放物面による集光： 平行ビーム→焦点

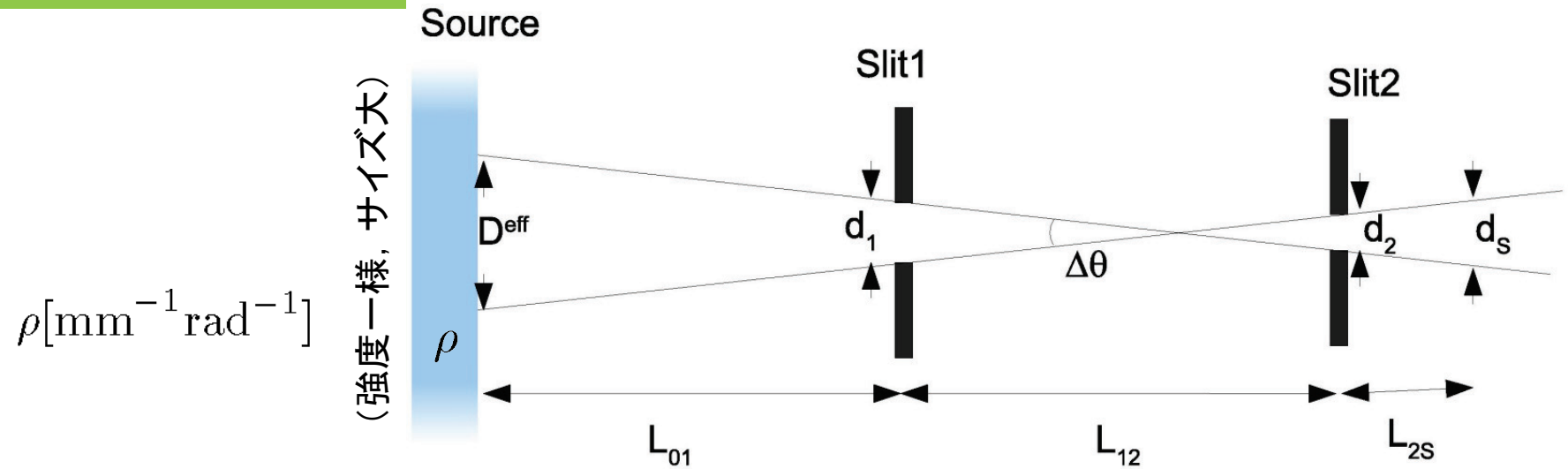


- 焦点=検出器面
  - 小角散乱, 斜入射小角散乱
- 焦点=試料位置
  - 微小試料, 試料内微小領域の観測

# 反射型微小ビーム集光の特徴

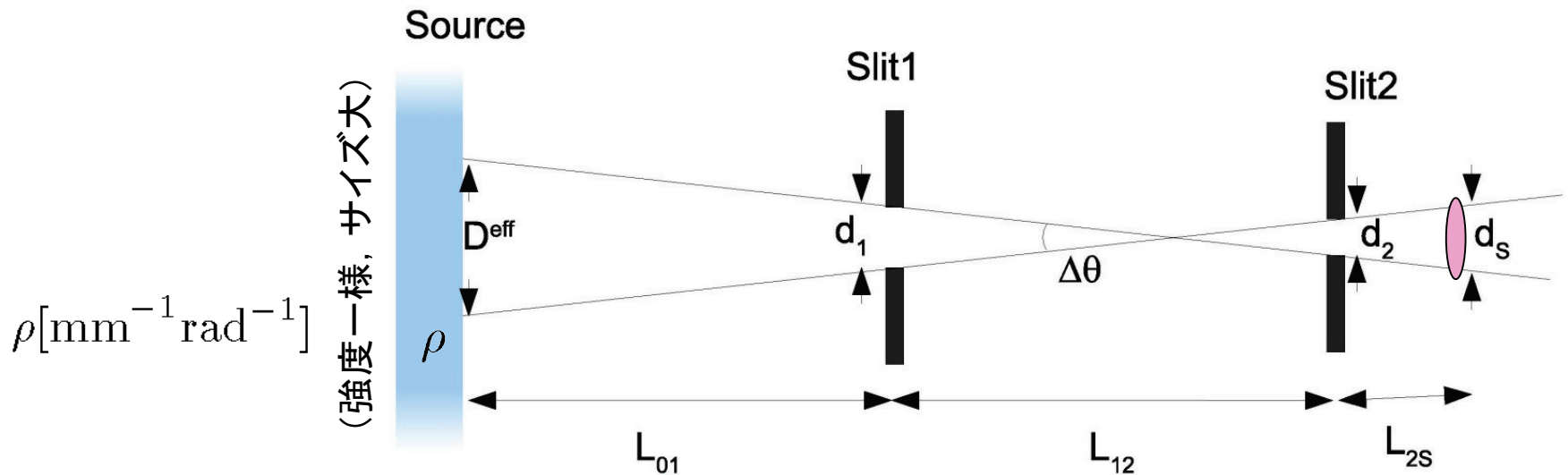
- 離れた位置から白色ビームを集光できる。
  - 集光位置手前に物を置けない系。
  - 試料環境がある場合. 小角散乱など.
- スリット・コリメーションに比べて発散角を稼げる。
  - 強度増
- 集光サイズの外では強度が桁落ちする。
  - 照射したい所にだけ当てる. バックグラウンド低減. コマ収差.
- 集光位置直前にピンホールを置けるなら不要
  - 集光型ガイド管 + 試料直前ピンホールがよい.
- 反射によりビーム方向が変わる
  - 建設済みのビームラインへの導入は簡単ではない.

# スリットによるコリメーション



- スリット設定とビーム強度, 発散角.
  - ビーム強度はスリット幅の積で決まる  $I = \frac{d_1 d_2}{L_{12}} \rho$  (1次元的強度)
  - 発散角は  $\Delta\theta = \frac{d_1 + d_2}{L_{12}}$   $I = -d_1(d_1 - L_{12}\Delta\theta)\rho/L_{12}$
  - 発散角を固定すると  $d_1 = d_2 = L_{12}\Delta\theta/2$  で強度が極大.
  - 試料位置でのビームサイズ  $d_s = \frac{L_{2S}}{L_{12}} d_1 + \frac{L_{12} + L_{2S}}{L_{12}} d_2$

# スリットによるコリメーション



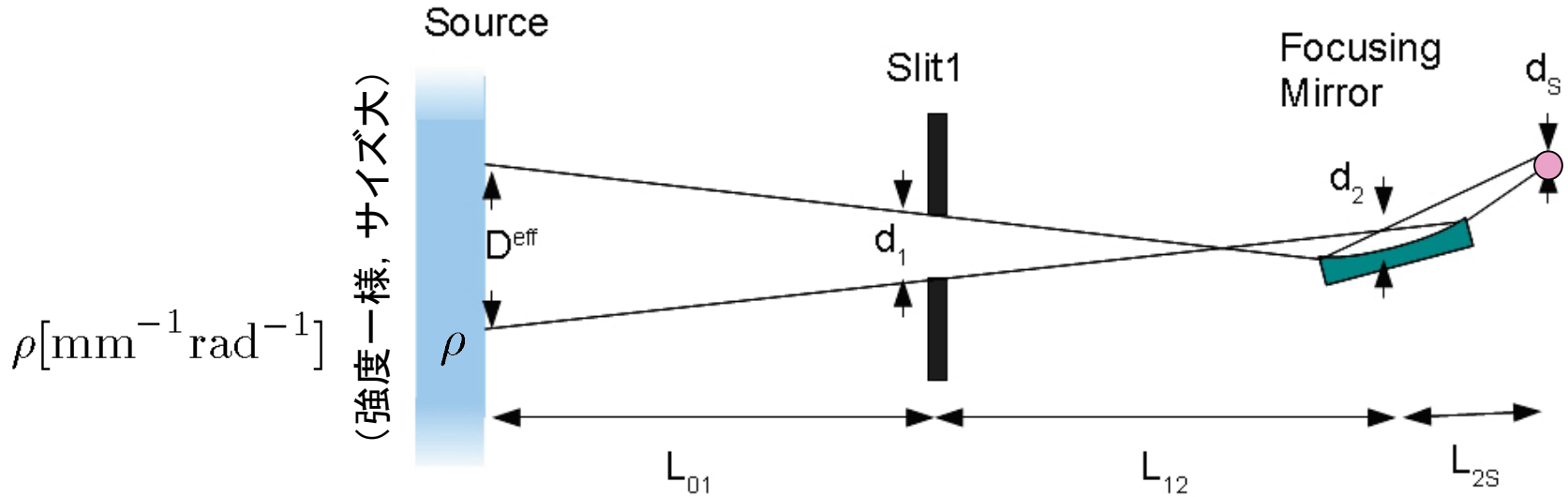
- 試料サイズ  $d_s$  に合わせてスリットを絞る。
  - $d_s$  によって最適な発散角, スリット設定が決まる。

$$\Delta\theta \equiv \frac{d_1 + d_2}{L_{12}} \rightarrow \frac{(L_{12} + 2L_{2S})d_S}{2L_{2S}(L_{12} + L_{2S})} \quad d_1 = \frac{L_{12}}{2L_{2S}}d_S \quad d_2 = \frac{L_{12}}{2(L_{12} + L_{2S})}d_S$$

- 試料位置のビーム強度 (1次元)

$$I = Ad_s^2 < \frac{d_s^2}{2L_{2S}}\rho \quad A = \frac{L_{12}}{2L_{2S}(L_{12} + L_{2S})}\rho$$

# ミラーによる集光の場合



## 集光ミラー系

- $d_1, d_2$ はスリットコリメーションよりもずっと大きく取れる.

$$d_1 = \frac{L_{12}}{L_{2S}} d_s \quad d_2 = L_{\text{mirror}} \sin \theta (\gg d_1)$$

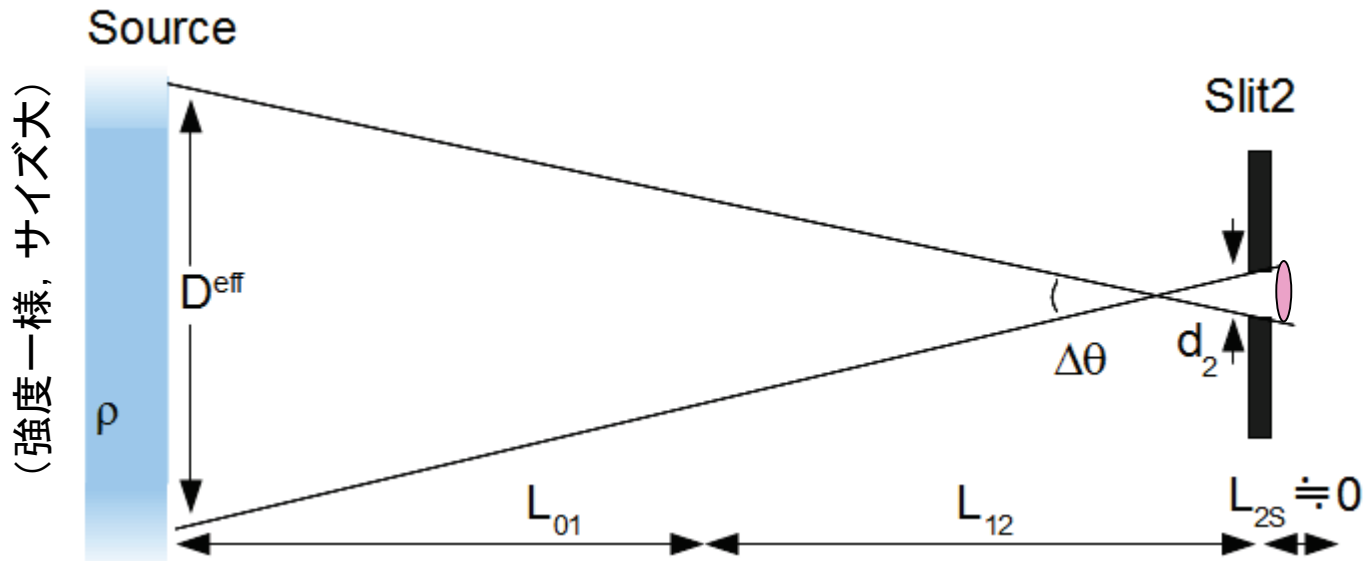
- 試料位置の強度(1次元)

$$I = \frac{d_1 d_2}{L_{12}} \rho \times R = \frac{d_s L_{\text{mirror}} \sin \theta}{L_{2S}} \rho R$$

発散角

$$\Delta \theta = \frac{d_2 + d_s}{L_{2S}}$$

# 直前スリットによるコリメーション



## 集光ミラー系

- ソース全体を見込む発散角が取れる.  $\Delta\theta = \frac{D^{\text{eff}} + d_2}{L_{01} + L_{12}}$
- Slitの後ろでは急激にビームサイズが広がる.

$$d_s = L_{2S}\Delta\theta + d_2$$

- Slit直後に集光するなら, 集光ミラー不要. 集光ガイド管の併用が吉.



# 微小点集光ミラーが使えるとき

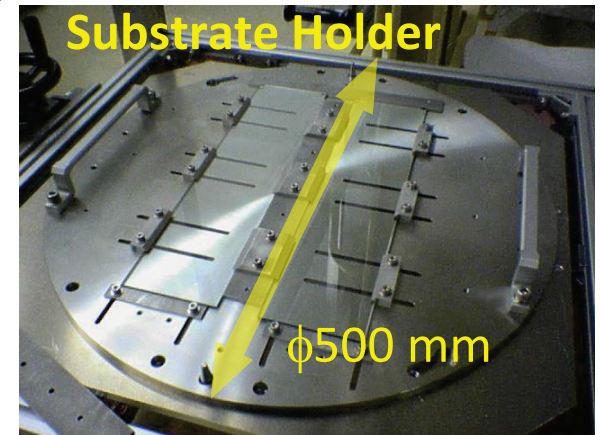
- 微小スポット以外にビームを当てたくないとき.
- 集光位置の直前にスリット等を置けないとき.
- ビームラインが変わってもよいとき.
- 白色ビームを集光したいとき

# High-Performance Supermirror at J-PARC

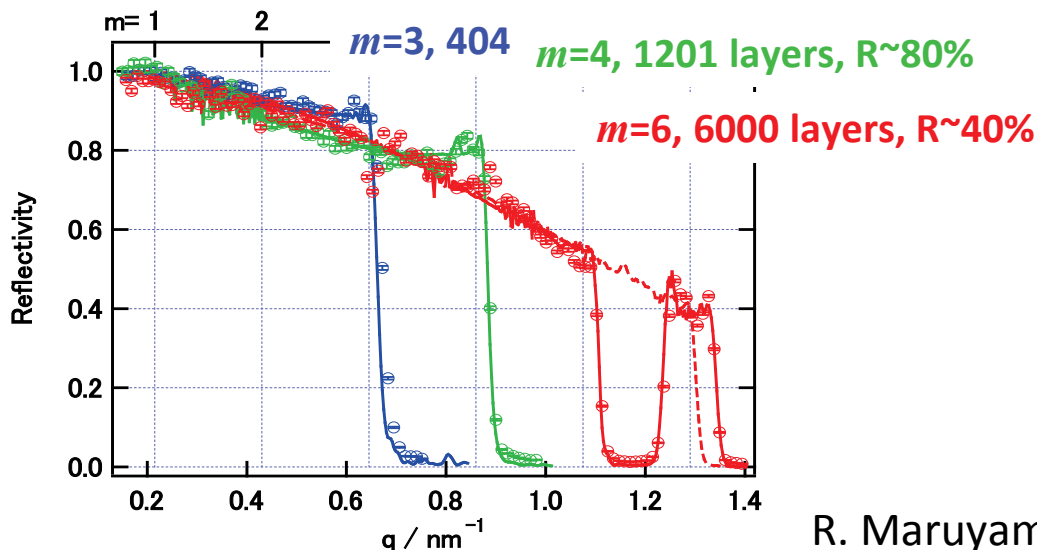
Ion Beam Sputtering Machine



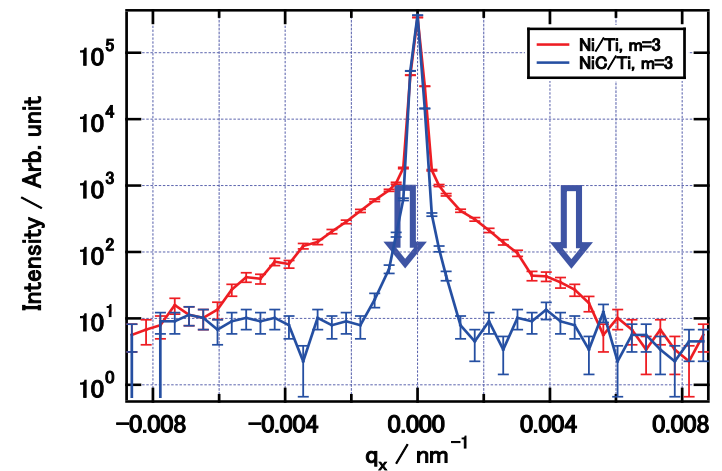
Large Sputering Area



High Qc and High Reflectivity

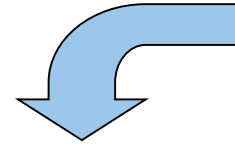
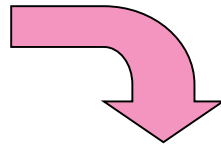


Reduction of diffuse scattering



# Focusing supermirror development

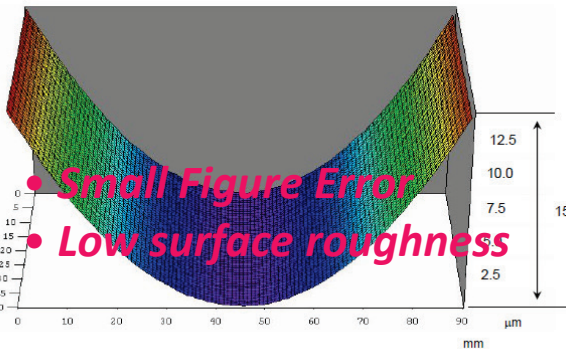
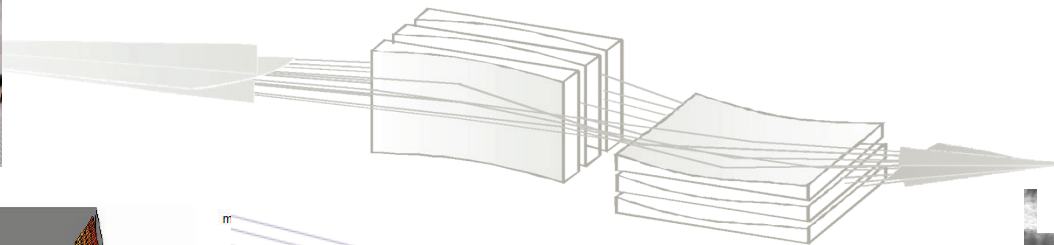
Ultraprecise  
Aspheric Surfaces  
by NC-Local Wet Etching



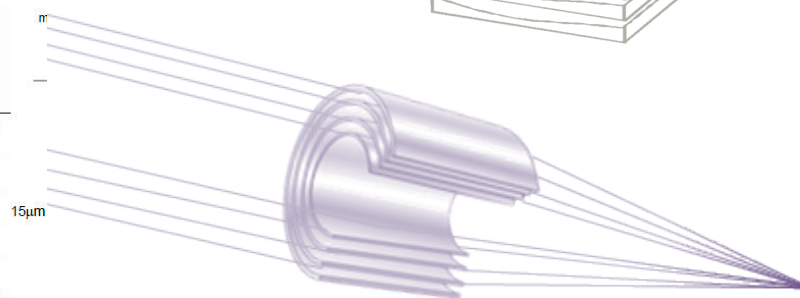
High Performance  
Supermirrors  
by ion beam sputtering



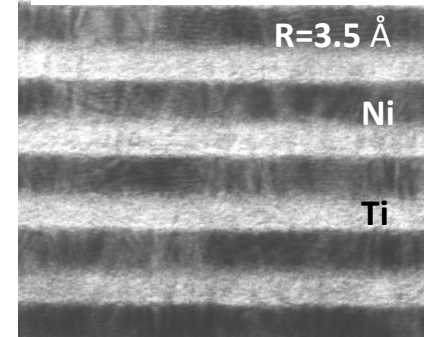
High performance  
Focusing supermirror



加工後形状 (評価領域90mm×40mm)



$m=6.7$  8000layers

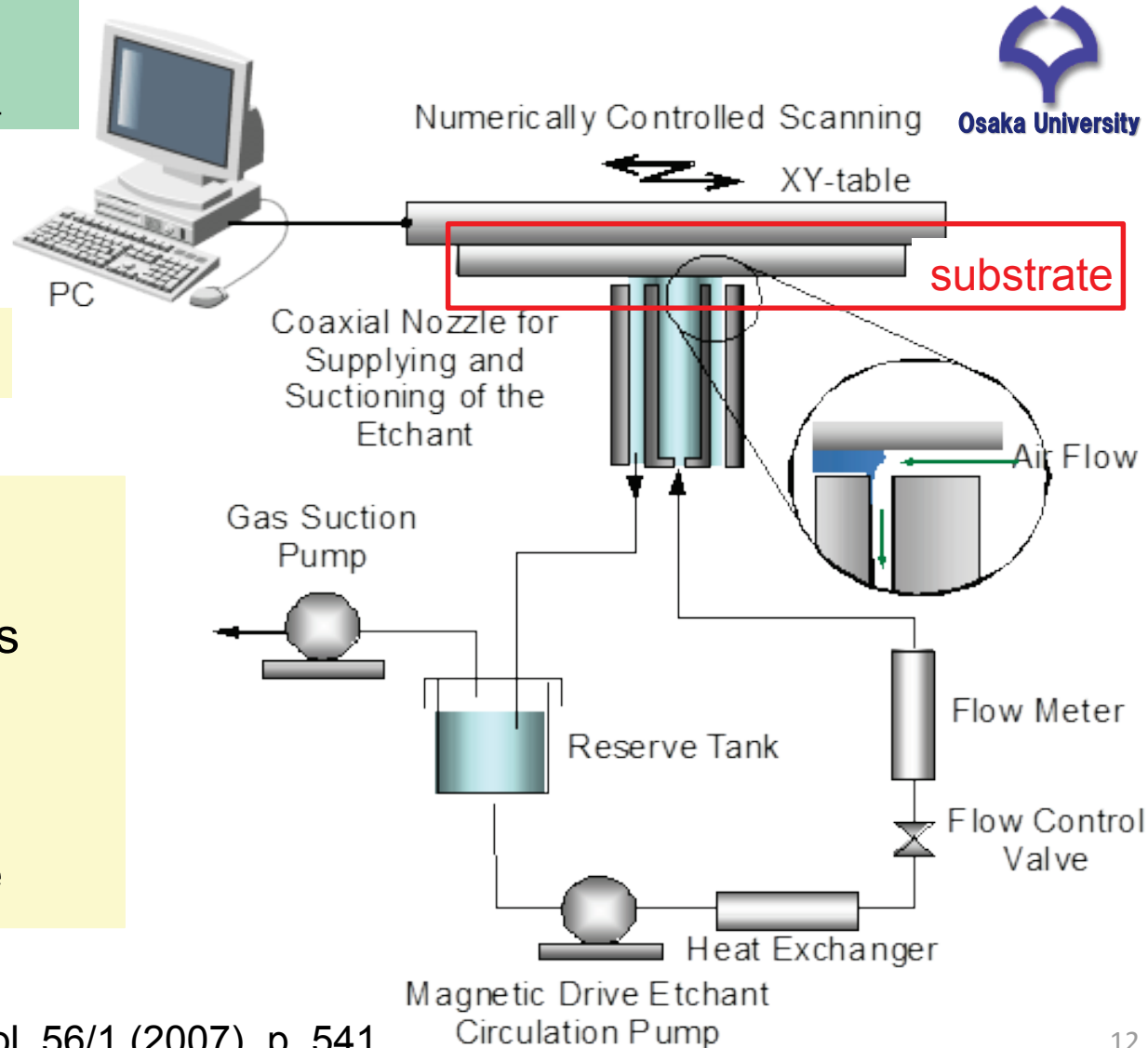


# Numerically Controlled Local-Wet-Etching (NC-LWE)

Ultraprecise figuring of a surface of quartz substrate

Etchant = HF acid

- Non-Contact process
- Purely chemical process
- ↓
- Stable process
- No mechanical damage



# Process of NC Local-Wet-Etching

## Figure Measurement

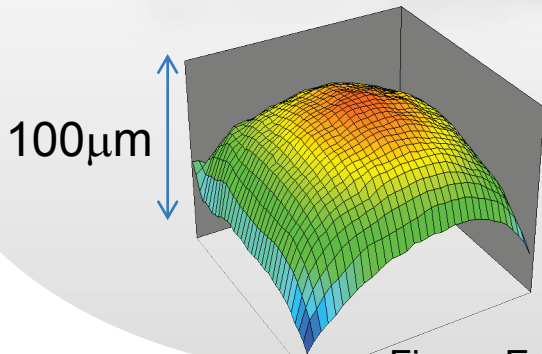
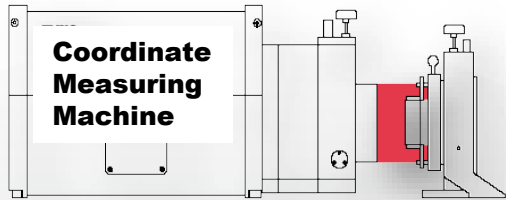


Figure Error

## Simulation

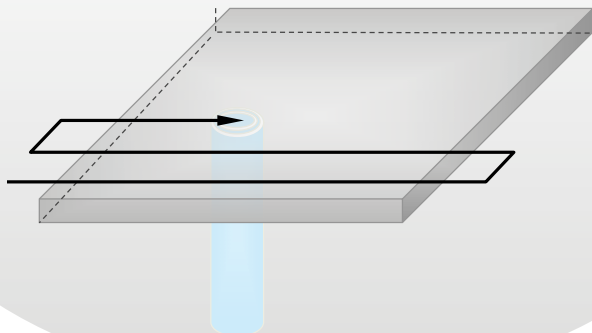


Convolution

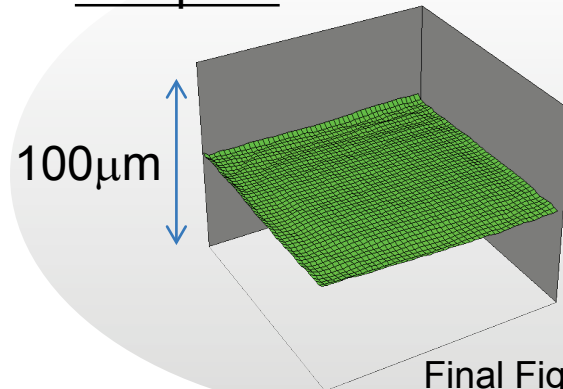
$$h(x, y) = f(x, y) \otimes g(x, y)$$

Total etching    Etching rate    Dwell Time

## NC local-wet etching



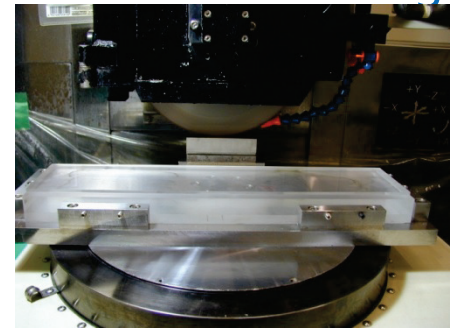
## Complete



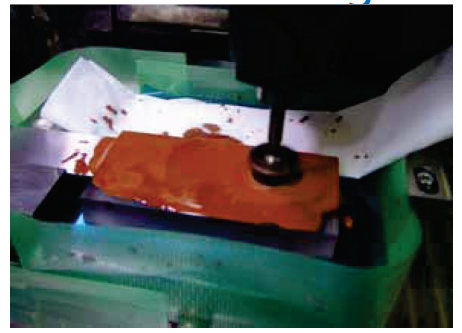
Final Figure Error

# High-Precision Aspheric Supermirror

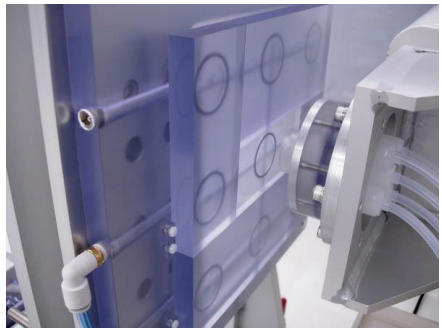
Precision Grinding



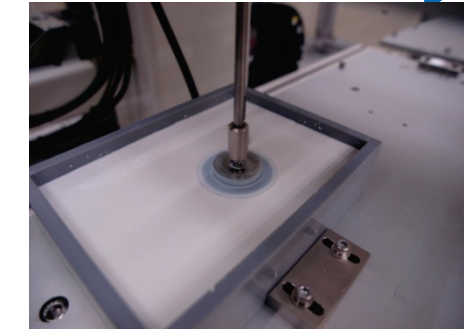
1st Polishing



NC-LWE



2nd&3rd Polishing



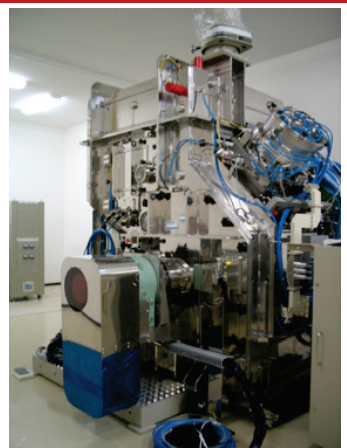
[The Purpose of Each Process]

Micrometric level figuring in short time	Removal of subsurface damage	Sub-micrometric level deterministic figuring	Removal of tool-mark & MSFR
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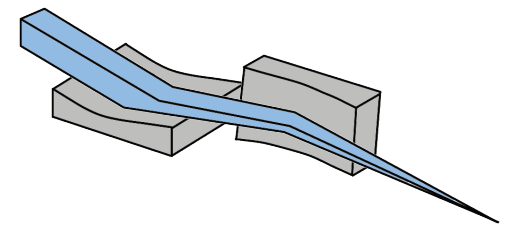
Ion Beam Sputtering



Deposition of NiC/Ti multilayer



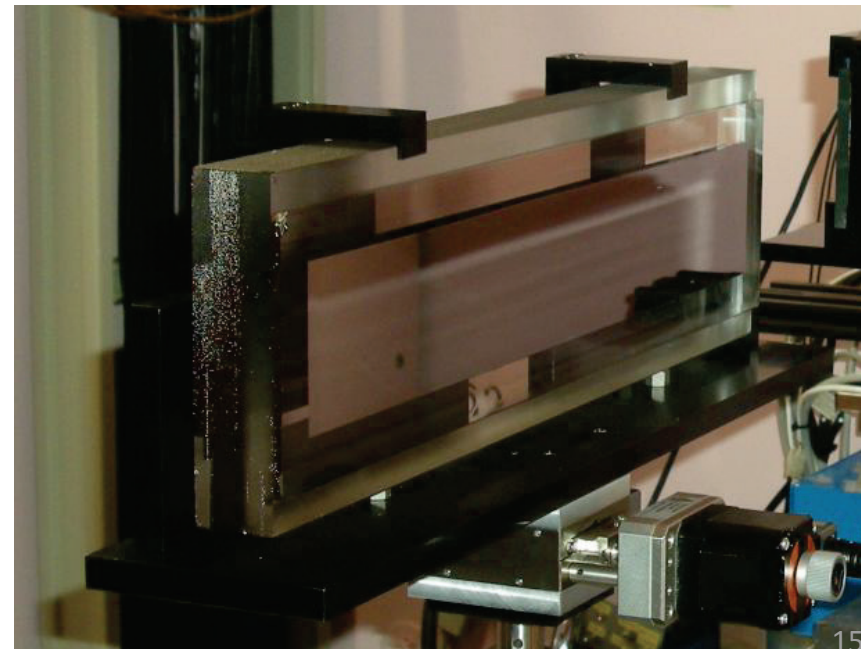
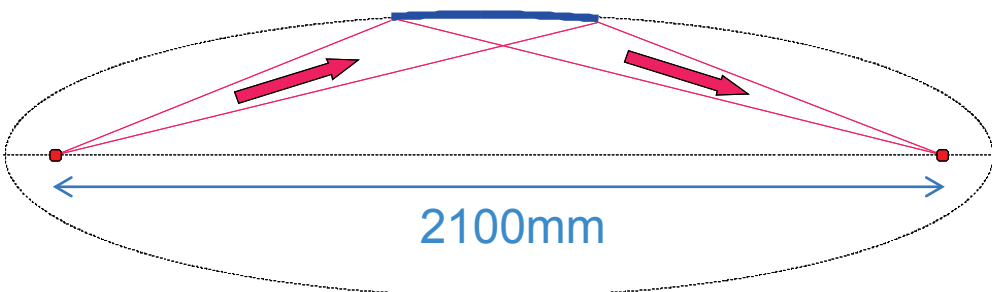
Aspherical Supermirror



high precision & high efficiency

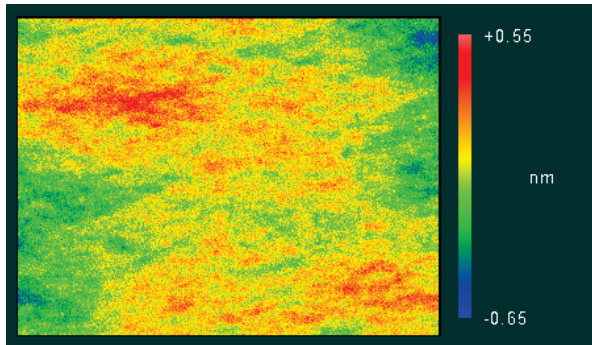
# 1-dimensional focusing supermirror

- 400mm L (elliptical) x 100mm H x 35mm T
- NiC/Ti Supermirror  $m=4$ 
  - Focal Lengths : 2100 mm = 1050mm + 1050mm
  - Incident angle 1.40 deg
  - $\lambda > 3.5 \text{ \AA}$
  - Beam acceptance  $\sim 10\text{mm}$
  - Beam divergence  $\sim 0.53\text{deg}$

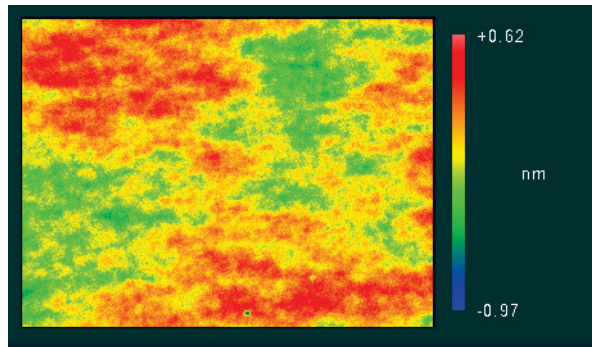


# Surface Roughness and Figure Errors

## Surface Roughness



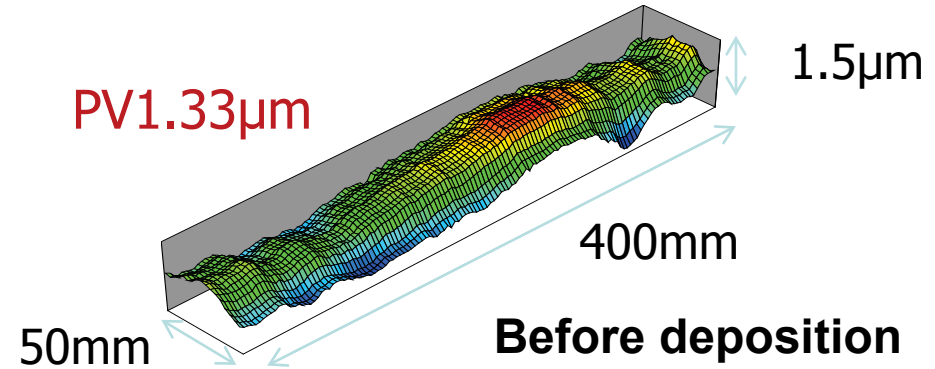
Before Deposition **0.151nm rms**



After Deposition **0.202nm rms**

(64 × 48μm<sup>2</sup>)

## Figure-Error

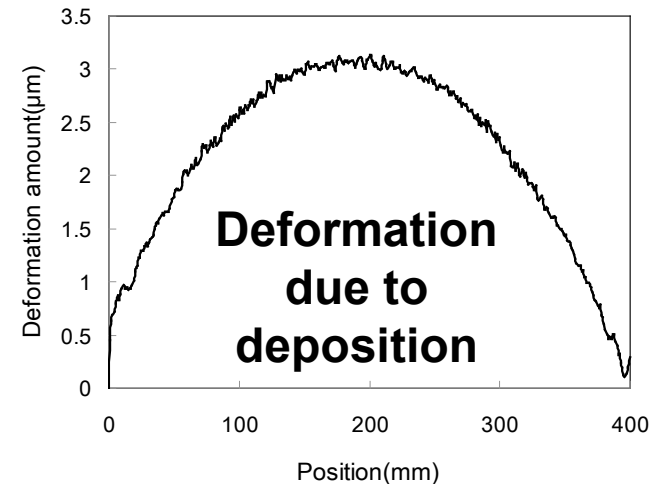


PV1.33μm

1.5μm

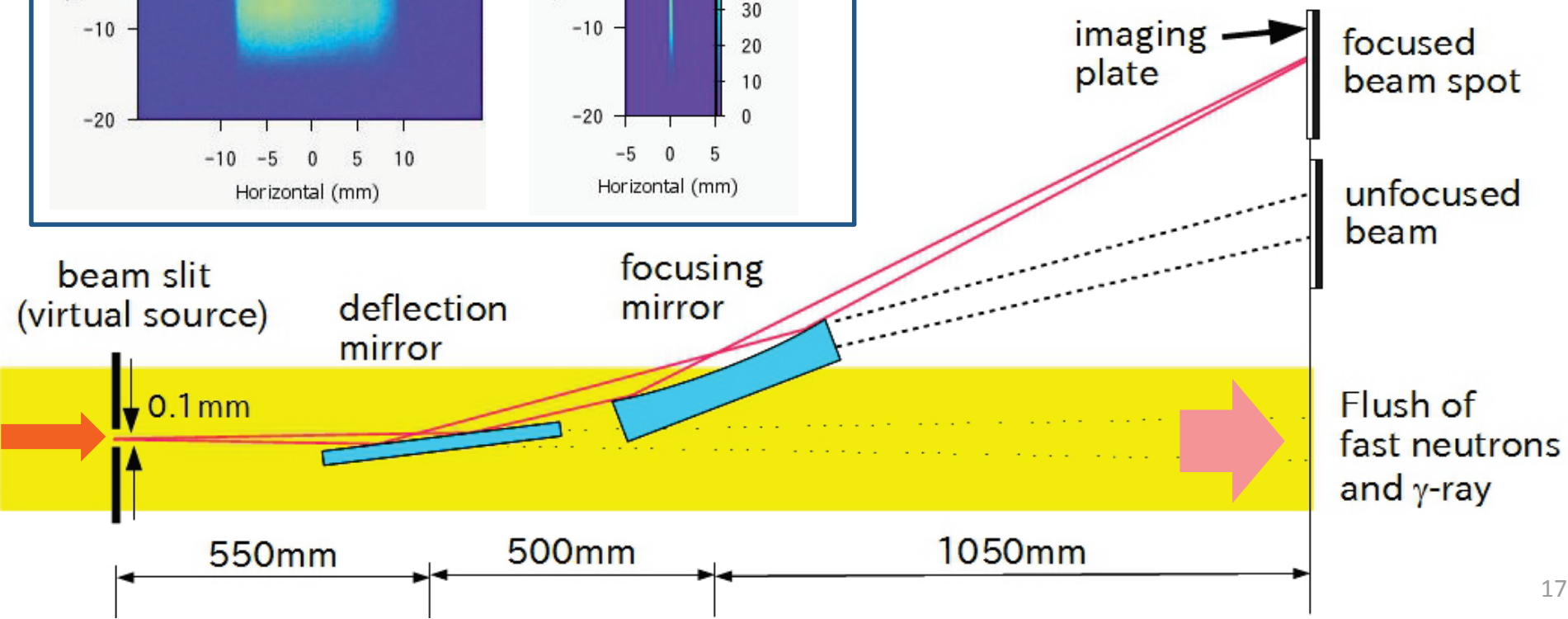
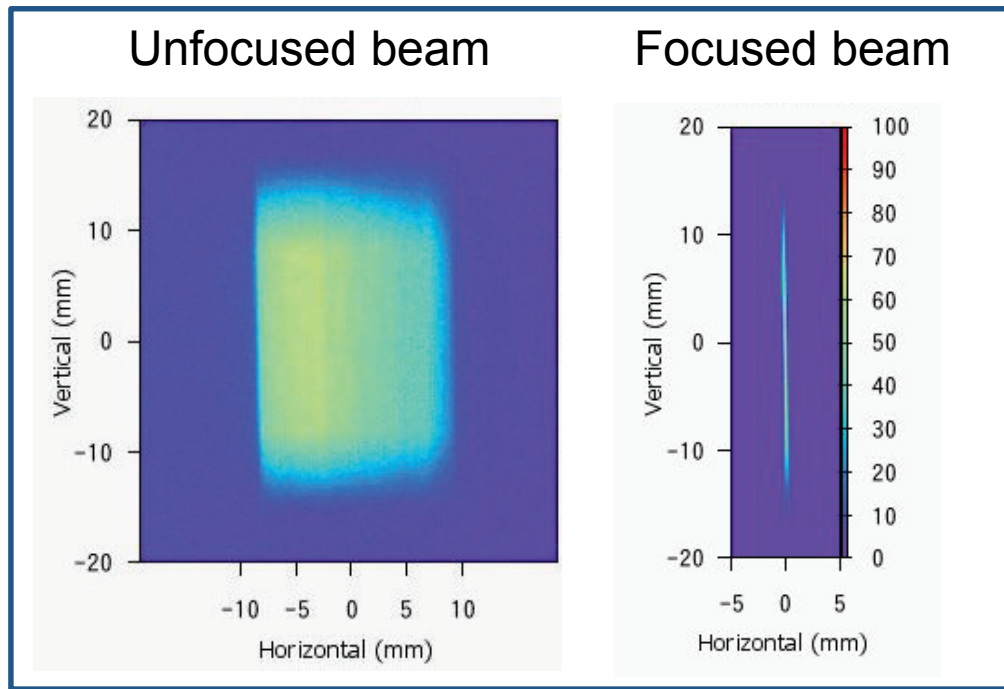
400mm

Before deposition



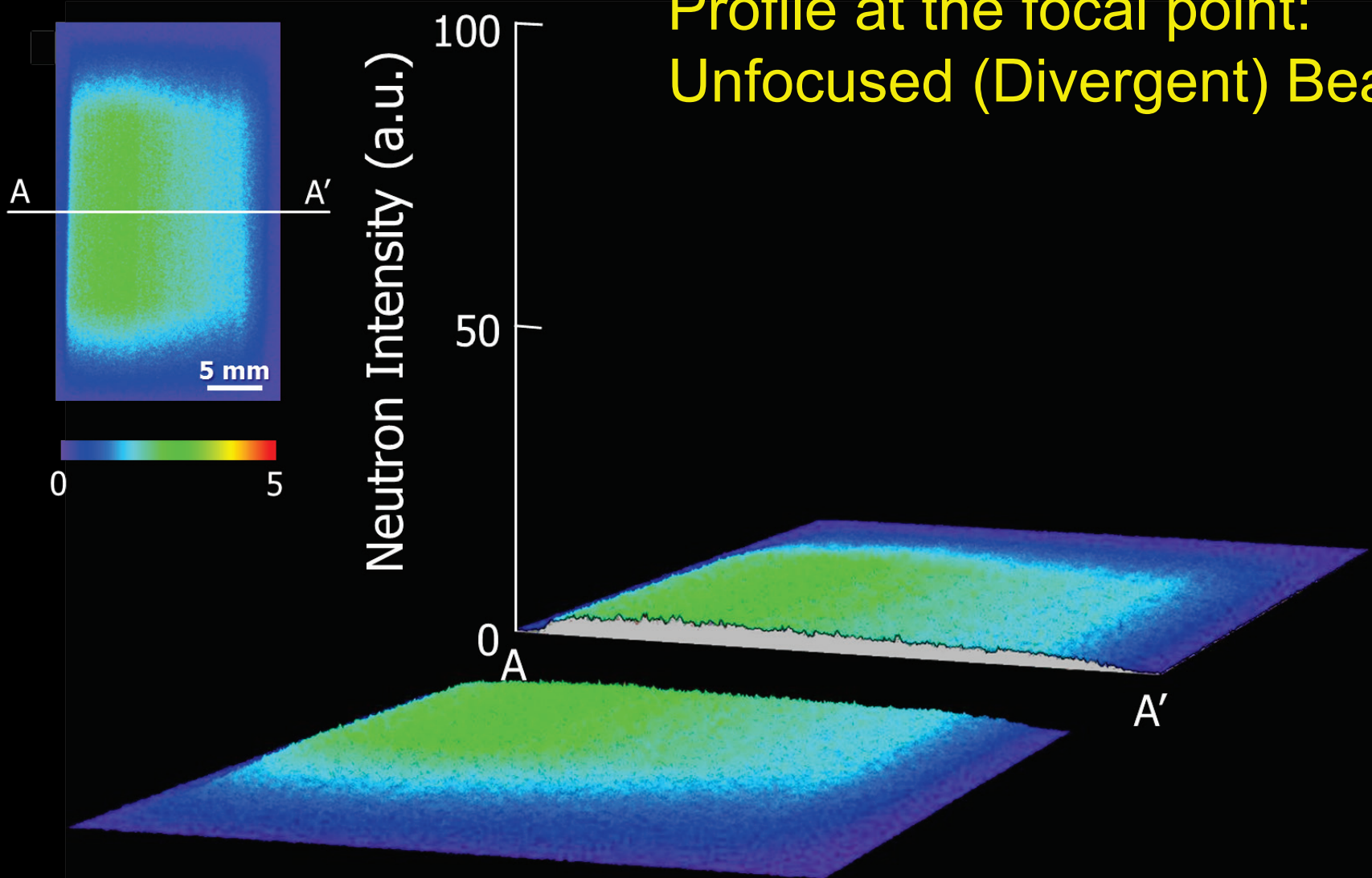


# Focusing Experiment with Pulsed Neutrons



# Focusing Experiment with Pulsed Neutrons

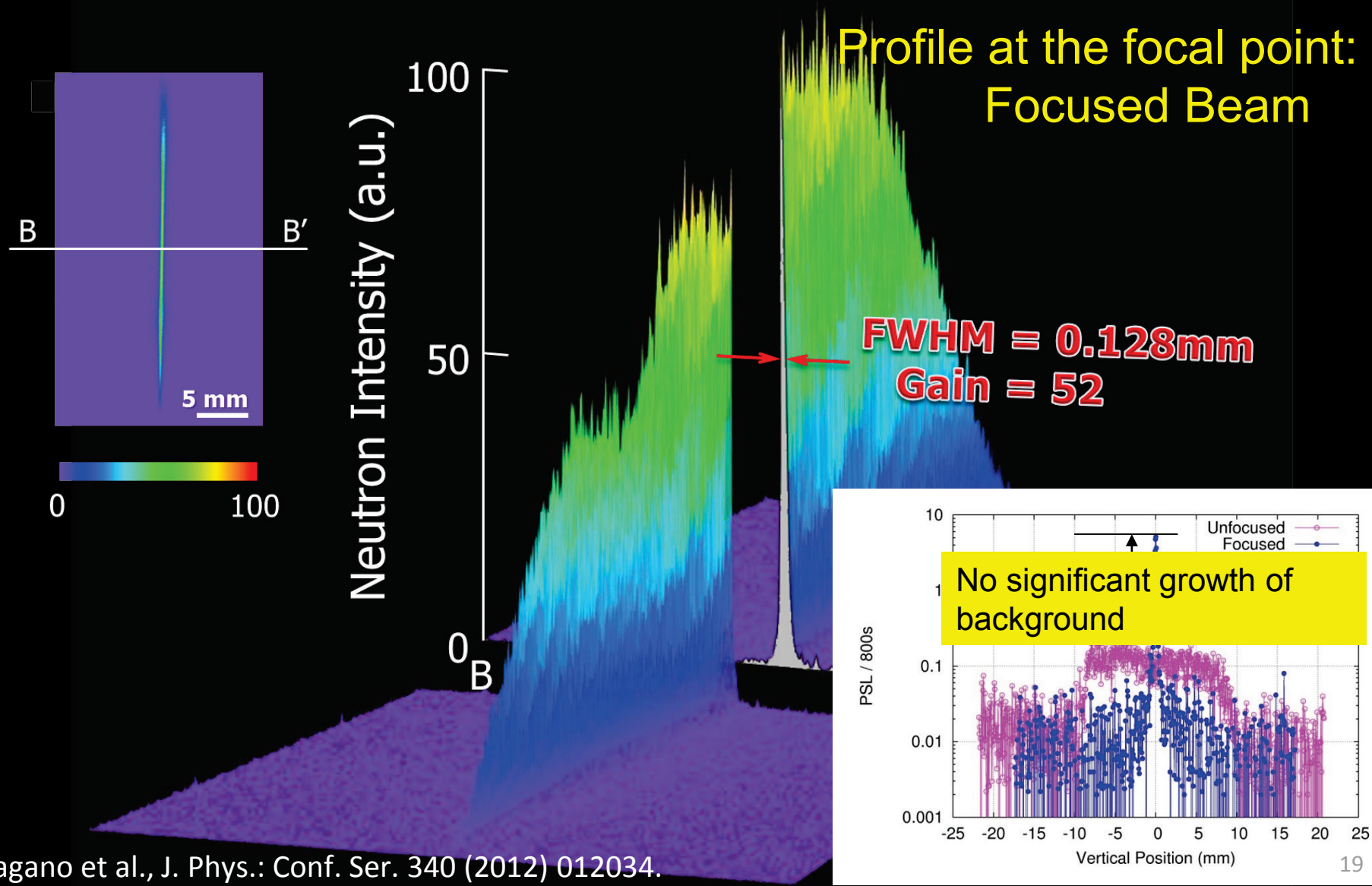
## - Spatial beam profile



Profile at the focal point:  
Unfocused (Divergent) Beam

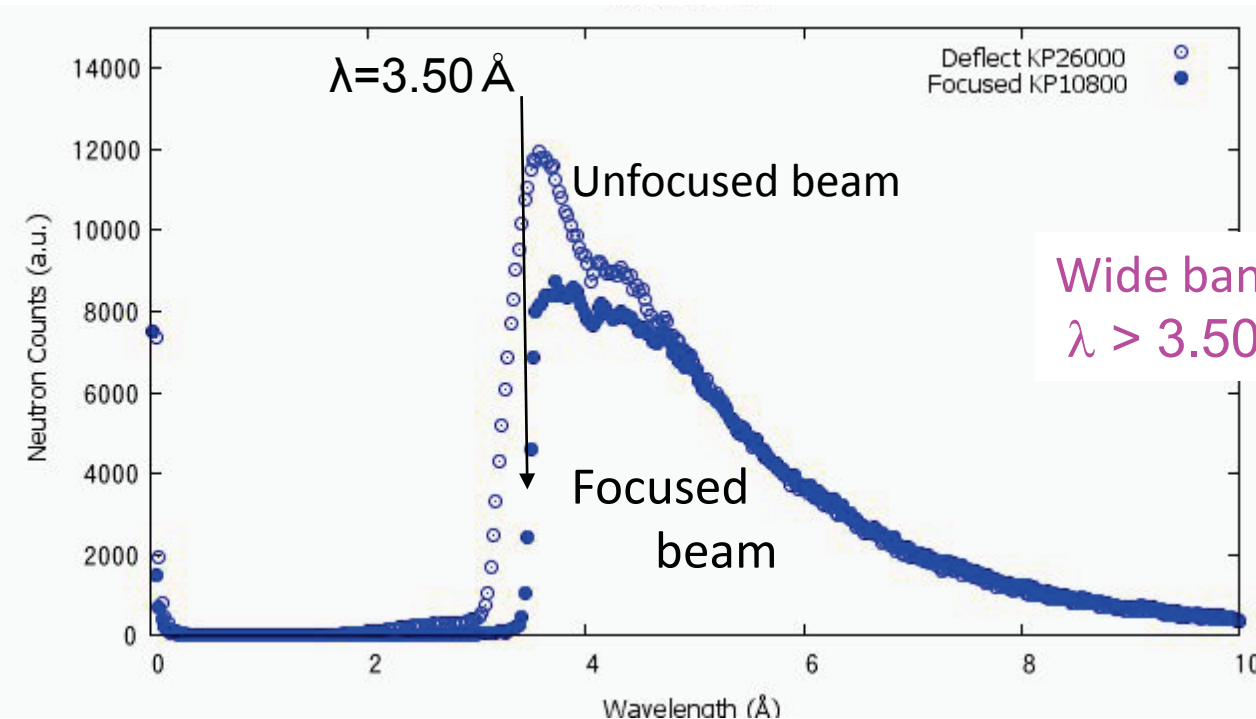
# Focusing Experiment with Pulsed Neutrons

## - Spatial beam profile



# Focusing Experiment with Pulsed Neutrons

## - Wavelength distribution

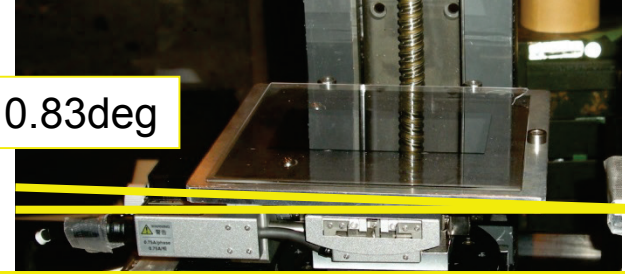


Wide band neutrons  
 $\lambda > 3.50 \text{ \AA}$  were focused.

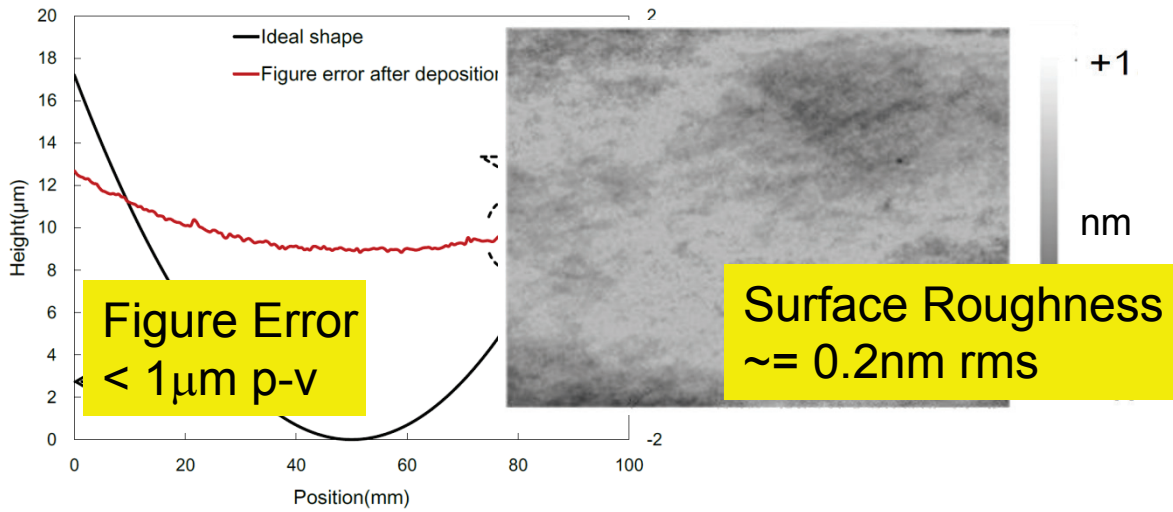
### Summary on focusing experiment:

- 1 dimensional beam focusing into  $< 0.15\text{mm}$
- intensity gain 52 at focused peak
- wideband focusing  $\lambda > 3.5 \text{ \AA}$
- No significant growth of background due to the mirror

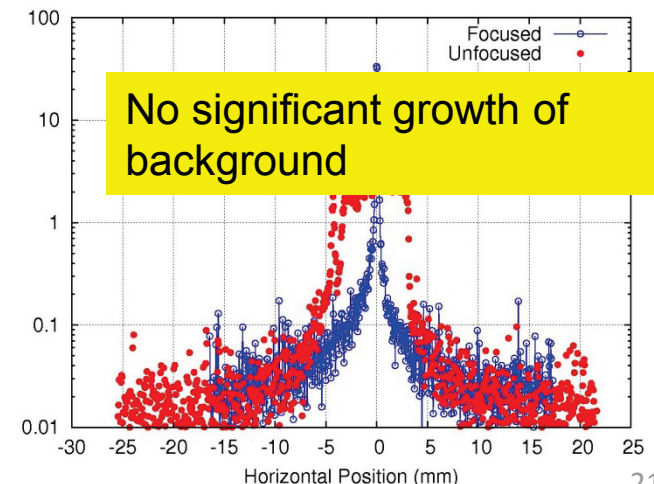
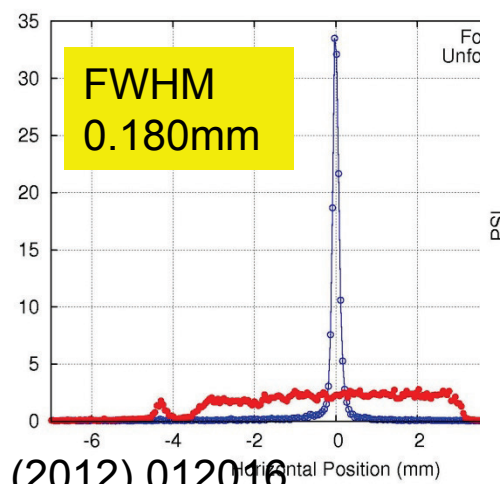
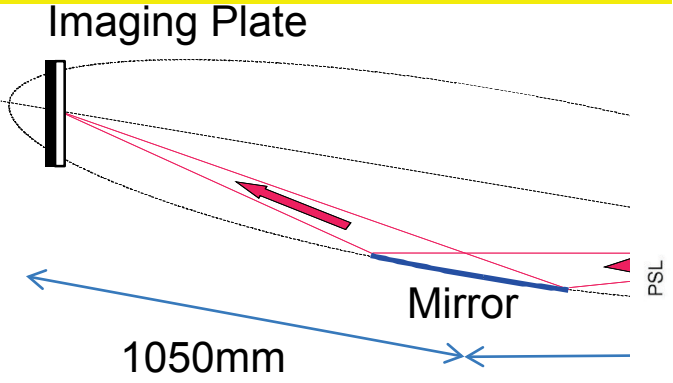
# Thin focusing mirrors for stacking



- Quartz substrate: 150x150x1.5mm
- 1-dimensionally elliptical shape
- NiC/Ti supermirror (m=3) deposited over 110 x 60 mm<sup>2</sup>
- Vertical focusing



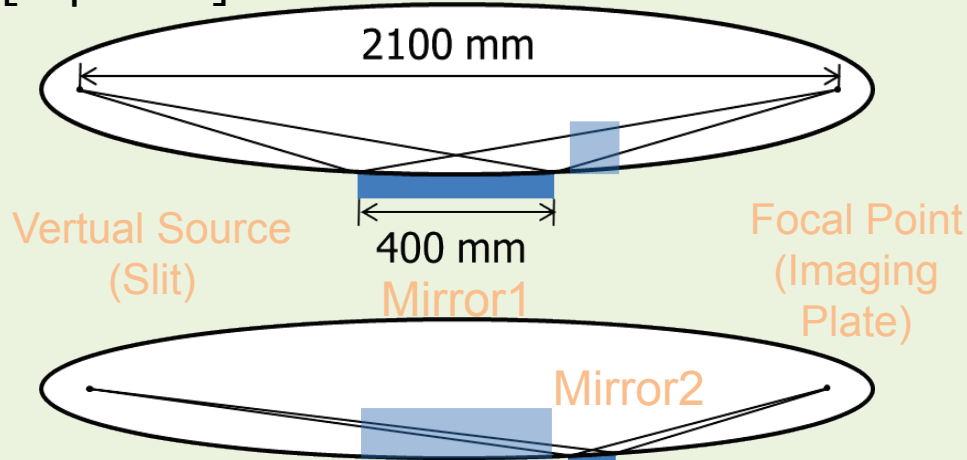
1 dimensional profiles obtained with an Imaging Plate



# 2-dimensional beam focusing

## Kirkpatrick-Baez (KB) Configuration

[Top View]

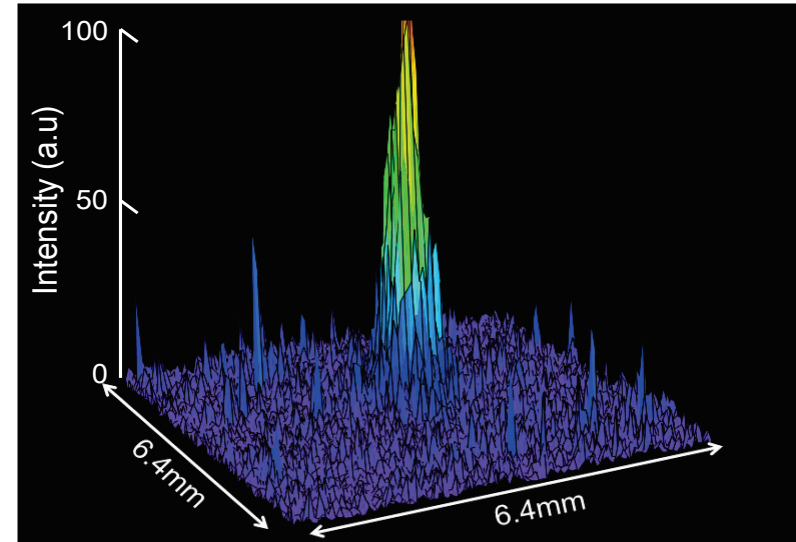


[Side View]

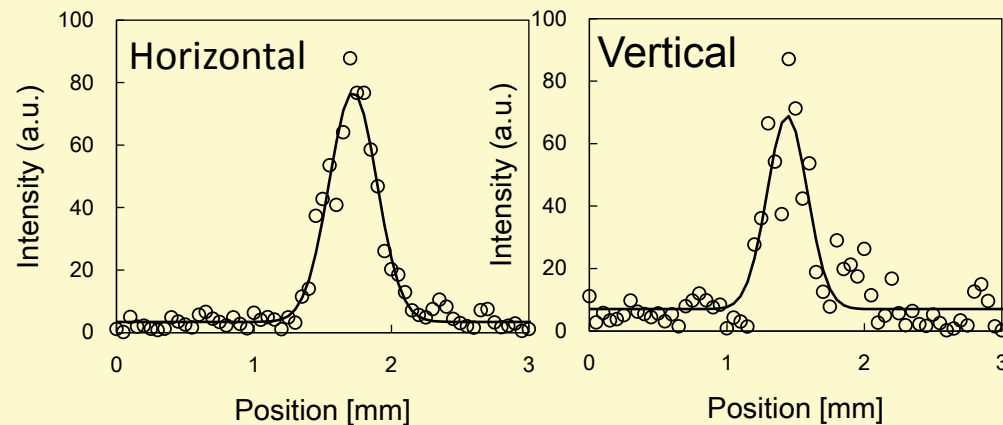
100 mm

### Parameters for focusing

Beam Line	BL10(NOBORU)
Focal Length(mm)	2100
Length of Mirror1(mm)	400
Length of Mirror2(mm)	100
Size of virtual source (mm)	0.5(H) x 1.0(V)
Contraction Rates	x1 (H), x0.45 (V)



Profile of Focused Beam



Focused Beam Size  $0.5 \times 0.5 \text{ mm}^2$  (FWHM) 22

# 2-dimensional beam focusing

Beam slit/Virtual source  
 $0.5 \text{ (h)} \times 1.0 \text{ (v)} \text{ mm}^2$

Deflecting Supermirror

Mirror1: 400mm

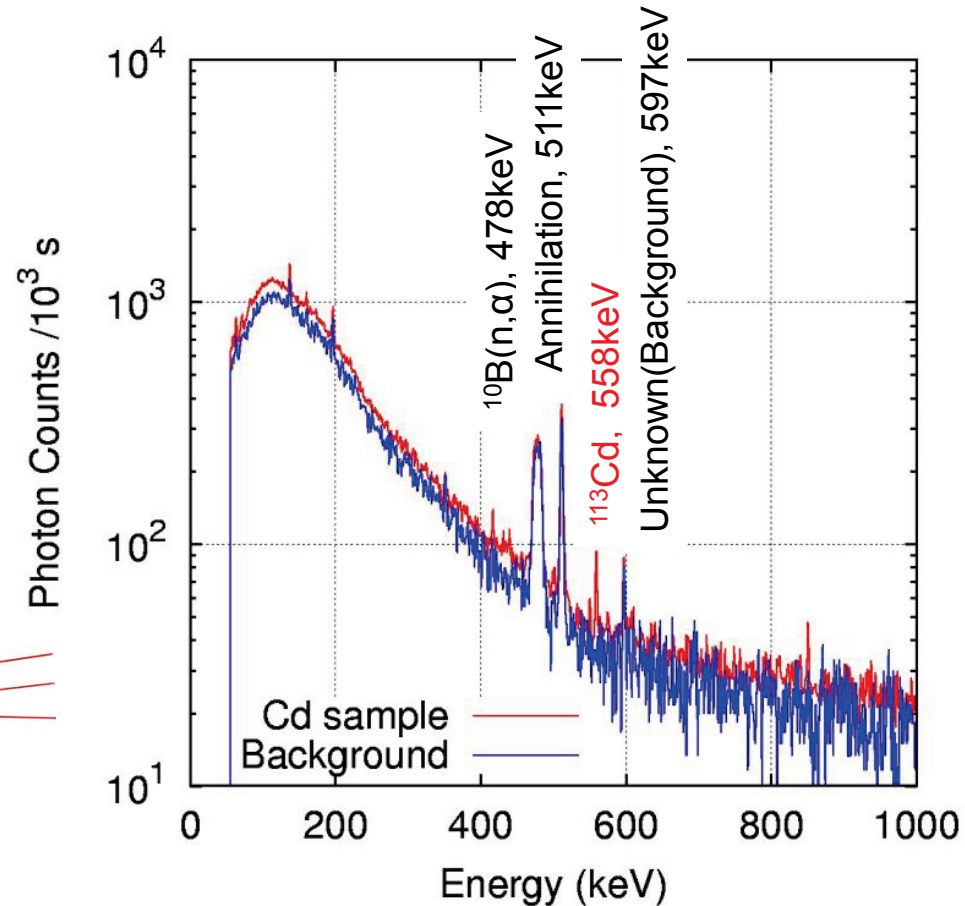
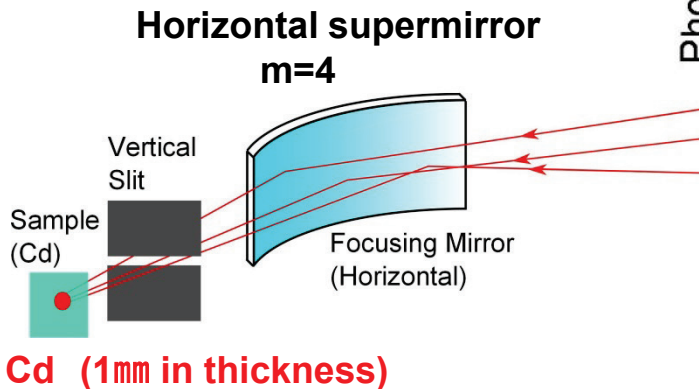
Mirror2: 100mm

Neutron beam

# Prompt $\gamma$ -Ray Activation Analysis at a small spot of a sample

- ★ Horizontally Focused 1x1mm<sup>2</sup>
- ★ Vertically Collimated
- ★ neutron intensity 10<sup>+3</sup> cps / 1mm<sup>2</sup>
- ★ Measuring time 2000sec(Cd), 600s(B.G.)
- ★ N-type Germanium Detector  
efficiency: 15% (at 1.33 MeV)  
resolution: 1.9 keV (at 1.33)

Ge detector  
with no  
shielding



A significant peak of Cd was successfully observed with no shield covering the detector

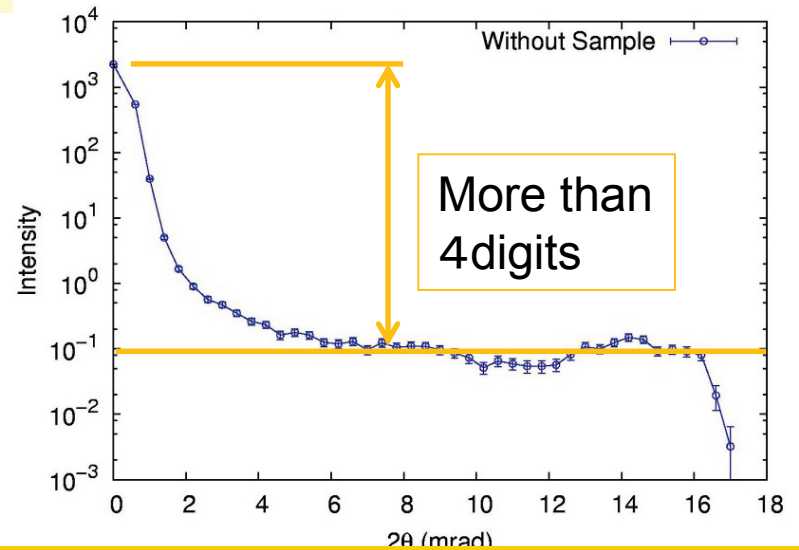
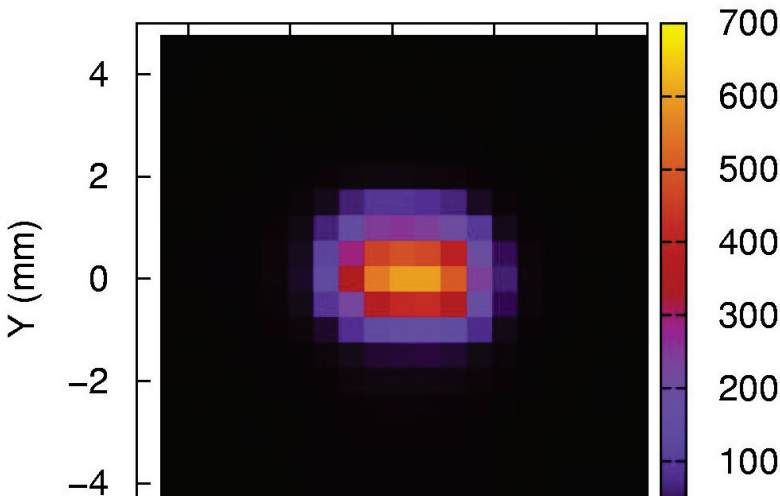
⇒ Useful for activation analyses of small regions of a sample 24



# Focusing for Compact small angle scattering

**PRELIMINARY**

- ★ J-PARC BL17 (PNR with coupled moderator)
- ★ **Vertically Focused**
- ★ **Horizontally Collimated**
- ★ **1.0x1.5mm<sup>2</sup>** @ Detector Position
- ★ Focal Length : 7430 + 3620 mm
- ★ Sample-Detector: 2500mm
- ★ RPMT scintillation detector



The Signal-to-Noise ratio can be improved by 2-D focusing and noise reductions on the RPMT detector.

# Summary

- Focusing mirror devices combining ultra-precise surface figuring and high-performance supermirror deposition with IBS.
- No figure-adjustment needed after fabrication.
- High focusing performance without growth of background.
- 2-dimensional focusing with the Kirkpatrick-Baez configuration.

# Summary

- Applications
  - PGAA at small regions of materials
  - Compact small angle scattering
- Under development
  - Grazing Incidence Small Angle Neutron Scattering
  - Angular Divergent Neutron Reflection
- Also applicable to
  - Samples in a high-pressure cell

# Collaborators

- J-ARC Center 
  - R. Maruyama, H. Hayashida, K. Soyama (design and supermirror deposition)
- Osaka University   
Osaka University
  - M. Nagano, F. Yamaga, N. Mitsushima, K. Yamamura (elliptic surfaces of quartz substrate)
- Support in beam experiments   
  
Comprehensive Research Organization for Science and Society  
Research Center for Neutron Science and Technology
  - Y. Kasugai, M. Katagiri, T. Shinohara, M. Harada, K. Oikawa, K. Aizawa, N. Miyata\*, Y. Sakaguchi\*, M. Mizusawa\*, K. Akutsu\*

\*: Comprehensive Research Organization for Science and Society (CROSS)

End